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WW Flack, G Newman, D Bernard, JC Rey, Y Granik, ... - Proc. SPIE, 1997 - ultratech.com
 ... pattern transfer operations such as dry **etching** and high ... information from each wafer,
 a special **reticle** with a ... 1) determination of the image of the **mask** at the ...

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Integrated device structure prediction based on model curvature - group of 2
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Y Granik, NB Cobb, FM Schellenberg - US Patent 6,643,616, 2003 - Google Patents
 ... (76) Inventors: **Yuri Granik**, 38838 Litchfield ... silicon yield is affected by several
 factors including **reticle**/maskpattern fidelity ... 20 resist and **etch** processing. ...

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FM Schellenberg, L Capodiec, B Socha - Proc. ACM/IEEE Design Automation Conf -
 doi.ieeecomputersociety.org

... by changing material properties or **etching** structures into the ... image corresponding
 to the modified **reticle** layout and ... polygons are added to the **mask** layout to ...

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Precision control of poly-gate CD by local OPC for elimination of microloading effect on 0.13-um ... - group of 5 »

MJ Li, S Maturi, P Dixit, DS Tucker, R Yang, H ... - spie.org
 ... systematic correction of these **distortions** by RET ... methodology that incorporates **lithographic** effects into a ... the dimensions resist effects, **etch** effects, **mask** ...

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Simulation for DUV-Lithography - group of 3 »

W Henke - Semiconductor Fabtech, 9th ed., Section - semiconductorfabtech.com
 ... resulting in an additional **pattern distortion** of resist ... ABOUT THE AUTHOR Wolfgang Henke received the Dipl ... He developed the **SOLID lithography simulator** and now ...
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Optimization of sub-100-nm designs for mask cost reduction

A Balasinski - Journal of Microlithography, Microfabrication, and ..., 2004 - link.aip.org
 ... These **distortions** cannot be completely corrected by **OPC** ... The author thanks Linard Karklin, Valery Axelrad ... correction, module 2: **Lithography simulation** based on ...
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TCAD development for lithography resolution enhancement - group of 5 »

LW Liebmann, SM Mansfield, AK Wong, MA Lavin, WC ... - IBM Journal of Research and Development, 2001 - research.ibm.com
 ... deliberate and proactive **distortion** of photomask ... of the **lithography** and **etch process**, significant lead ... necessary tradeoffs between **lithographic** enhancement and ...
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Integrating design data with manufacturing data: why you want to use a universal data model(UDM) - group of 5 »

WR Erck - Proceedings of SPIE, 2003 - si2.org
 ... Make sure designers use them 3. **Mask/Lithography/Wafer Etch** Models for ... and expanded by the author of this ... for optical and process **distortions** in manufacturing ...
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Phase shifting mask topography effect correction based on near-field image properties - group of 3 »

A Kroyan - US Patent 6,794,096, 2004 - Google Patents
 ... MOPC) Flow To Include **Mask Writer** Issues", IPCOM000009586D ... One advance in **lithography** called phase shifting is ... compensating for some litho-graphic **distortions**. ...
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Photomask Technology

MMMC Center - spie.org
 ... advances needed in the **mask writers**, inspection, metrology ... optimization and dry **etch** screening on ... 35 am: Chromeless phase **lithography reticle** defect inspection ...
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(book) Causal Analysis of Systematic Spatial Variation in Optical Lithography

H Zhang - 2002 - bcam.berkeley.edu
 ... variability of the plasma **etch process**, and that ... terms may cause image **distortion** or shifting ... of the most important sources of systematic spatial **lithography** ...
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[Google Patent Search Help](#)**Patent Search**Patents 1 - 7 of 7 on **compensate lithographic distortions " mask/reticle"**. (0.31 seconds)**Electron beam shot linearity monitoring**

US Pat. 6721939 - Filed Feb 19, 2002 - Taiwan Semiconductor Manufacturing Co., Ltd

OPC applies systematic changes to mask geometries to **compensate** for the nonlinear **distortions** caused by optical diffraction and resist process effects. ...**Site control for OPC**

US Pat. 7073162 - Filed Oct 31, 2003 - Mentor Graphics Corporation

To improve the pattern fidelity, changes can be made to the **mask/reticle** patterns that **compensate** for the expected optical **distortions**. ...**Lithographic apparatus, device manufacturing method, and device manufactured thereby**

US Pat. 6809797 - Filed Mar 29, 2002 - ASML Netherlands B.V.

... 15 25 40 rotation of the **mask (reticle)**; 45 adjustment of the mask height (eg to **compensate** ... and the **lithographic** error LR asymmetry will be reduced. ...**Exposure apparatus and exposure method**

US Pat. 6721033 - Filed Jul 13, 2000 - Nikon Corporation

Then at step S302 (masking step), a **mask (reticle)** having the designed pattern is formed. In step S303 (wafer fabrication step), wafers are produced from ...**Compact photoemission source, field and objective lens arrangement for high throughput electron beam lithography**

US Pat. 6215128 - Filed Mar 18, 1999 - Etec Systems, Inc.

... and stages for supporting the substrate and the **mask (reticle)**. ... lenses of the photolithography subsystem can be used to **compensate** for distortion ...**Lithographic apparatus, device manufacturing method, and device manufactured thereby**

US Pat. 6633366 - Filed Aug 10, 2001

Since these beam- **mask (reticle)**. Further improvement is impossible by short-lets only interfere in a small area, the Coulomb interaction ening the ...**METHOD OF MANUFACTURING A DEVICE BY EMPLOYING A LITHOGRAPHIC APPARATUS INCLUDING A SLIDING ELECTRON-OPTICAL ELEMENT**

US Pat. 7102732 - Filed Apr 28, 2003 - Elith LLC

This decreases the Coulomb interaction and the chromatic aberration, which is large due to the plasmon losses in the **mask (reticle)**. ...

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... and Monte Carlo simulation technique", Journal of Applied Physics 84(8), 1998, pp. ... which is large due to the plasmon losses in the mask (reticle). ...

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